

**AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1           Claim 1 (Currently Amended): A chuck equipment comprising  
2           a plate-shaped base,  
3           a first electrode to which a first voltage is applied, and  
4           a second electrode to which a second voltage different from the first voltage in  
5           magnitude is applied, the first and second electrodes being insulated from each other  
6           and arranged on a surface of said base, said first and second electrodes having a  
7           substrate thereabove and said substrate is disposed in an electric field formed between  
8           said first and second electrodes, when said first and second voltages are applied, for  
9           holding said substrate onto said first and second electrodes,  
10           wherein said surfaces of said first and second electrodes are exposed,  
11           wherein the chuck equipment is constructed in such a manner that said  
12           substrate is placed on the surface of said chuck equipment on which said first and  
13           second electrodes are arranged to cause said substrate to be brought into contact with  
14           said first and second electrodes.

Claims 2-3 (Canceled)

1 Claim 4 (Currently Amended): The chuck equipment according to claim [[2]]  
2 1, wherein the surface of said base is flush with the surfaces of said first and second  
3 electrodes.

1 Claim 5 (Currently Amended): The chuck equipment according to claim [[2]]  
2 1, wherein an insulating convexity portion is arranged between said first and second  
3 electrodes.

1 Claim 6 (Currently Amended): The chuck equipment according to claim [[2]]  
2 1, wherein said first and second electrodes have a protective film on the surfaces  
3 thereof and said protective film is exposed.

Claim 7 (Canceled)

1 Claim 8 (Currently Amended): The chuck equipment according to claim [[2]]  
2 1, wherein said first electrode is spaced apart from said second electrode by 2mm or  
3 less.

1 Claim 9 (Currently Amended): The chuck equipment according to claim [[2]]  
2 1, wherein said first and second electrodes are 4mm or less in width.

1 Claim 10 (Currently Amended): The chuck equipment according to claim [[2]]  
2 1, comprising a plurality of said first and second electrodes arranged thereon, wherein  
3 region where said first and second electrodes are alternately arranged is provided.

1 Claim 11 (Currently Amended): The chuck equipment according to claim [[2]]  
2 1, comprising a third electrode to which a third voltage different from said first and  
3 second voltages is applied.

1 Claim 12 (Currently Amended): A vacuum processing apparatus comprising a  
2 vacuum chamber in which the chuck equipment according to claim [[2]] 1 is  
3 arranged.

1 Claim 13 (Original): The vacuum processing apparatus according to claim 12,  
2 comprising a power supply for establishing an electric field of  $1.0 \times 10^6 \text{V/m}$  or  
3 greater between said first and second electrodes.

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Reply to OA of **November 19, 2003**

1           Claim 14 (Original): The vacuum processing apparatus according to claim 13,  
2           wherein a protective plate is arranged around said chuck equipment, and the vacuum  
3           processing apparatus is constructed in such a manner that a substrate is placed on said  
4           chuck equipment to cause said substrate to be accommodated in said protective plate.

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